

**RESTATEMENTS AND AMENDMENTS**

**In the Claims:**

The following is a list of claims currently pending in this application and their current status. This listing of claims replaces all prior versions and listings in this application.

1. (Original) An immersion lithographic system for patterning a work piece arranged at an image plane and covered at least partly with a layer sensitive to electromagnetic radiation, comprising:
  - a source emitting electromagnetic radiation onto an object plane,
  - a modulator, adapted to receive and modulate said electromagnetic radiation at said object plane in accordance to an input pattern description, and to relay said electromagnetic radiation toward said work piece,
  - an immersion medium contacting at least a portion of an immersion optics of said lithographic system and a portion of said work piece, wherein said immersion medium is supplied through at least one orifice arranged in said immersion optic.
2. (Original) The apparatus according to claim 1, wherein said modulator is an SLM.
3. (Original) The apparatus according to claim 2, wherein said SLM comprises reflective pixels.
4. (Original) The apparatus according to claim 3, wherein said reflective pixels are micromirrors.
5. (Previously presented) The apparatus according to claim 1, wherein said modulator is an acoustooptical modulator.
6. (Original) The apparatus according to claim 1, wherein said source emitting electromagnetic radiation is an excimer laser.
7. (Original) The apparatus according to claim 1, further comprising a porous or fibrous material through which said immersion medium is supplied.

8. (Original) The apparatus according to claim 1, further comprising at least one immersion medium removal orifice.
9. (Original) The apparatus according to claim 8, further comprising a porous or fibrous material through which said immersion medium is removed.
10. (Currently amended) The apparatus according to claim 7 [~~or 9~~], wherein said ~~at~~ porous material is kept incompletely saturated with said immersion medium.
11. (Original) An immersion lithographic system for patterning a work piece arranged at an image plane and covered at least partly with a layer sensitive to electromagnetic radiation, comprising
  - a source emitting electromagnetic radiation onto an object plane,
  - a mask arranged at said object plane to relay said electromagnetic radiation toward said work piece,
  - an immersion medium contacting at least a portion of an immersion optics of said lithographic system and a portion of said work piece, wherein said immersion medium is supplied through at least one orifice arranged in said immersion optics.
12. (Original) The apparatus according to claim 11, wherein said source emitting electromagnetic radiation is an excimer laser.
13. (Original) The apparatus according to claim 11, further comprising a porous or fibrous material through which said immersion medium is supplied.
14. (Original) The apparatus according to claim 11, further comprising at least one immersion medium removal orifice.
15. (Original) The apparatus according to claim 14, further comprising a porous or fibrous material through which said immersion medium is removed.
16. (Currently amended) The apparatus according to claim 13 [~~or 15~~], wherein said at porous or fibrous material is kept incompletely saturated with said immersion medium.
17. (Original) An immersion lithographic system for patterning a work piece arranged at an image plane and covered at least partly with a layer sensitive to

electromagnetic radiation, comprising

- a source emitting electromagnetic radiation onto an object plane,
- a modulator, adapted to receive and modulate said electromagnetic radiation at said object plane in accordance to an input pattern description and to relay said electromagnetic radiation toward said work piece,
- an immersion medium contacting at least a portion of a objective lens of said lithographic system and a portion of said work piece, wherein an area of said contacting is restricted by capillary forces.

18. (Original) The immersion lithography system according to claim 17, further comprising a immersion medium reservoir for supplying immersion medium to said portion of said objective lens and said workpiece.

19. (Original) The immersion lithography system according to claim 18, wherein said immersion medium is supplied through a porous or fibrous material.

20. (Original) An immersion lithographic system for patterning a work piece arranged at an image plane and covered at least partly with a layer sensitive to electromagnetic radiation, comprising

- a source emitting electromagnetic radiation onto an object plane,
- a mask, adapted to receive and modulate said electromagnetic radiation at said object plane and to relay said electromagnetic radiation toward said work piece,
- an immersion medium contacting at least a portion of a final lens of said lithographic system and a portion of said work piece, wherein an area of said contacting is restricted by capillary forces.

21. (Currently amended) The immersion lithography system according to claim 17, further comprising **[[a]] an** immersion medium reservoir for supplying immersion medium to said portion of said objective lens and said workpiece.

22. (Original) The immersion lithography system according to claim 18, wherein said immersion medium is supplied through a porous or fibrous material.

23. (Cancelled)

24. (Currently amended) A method for patterning a workpiece arranged at an image plane and covered at least partly with a layer sensitive to electromagnetic radiation, including the actions of:

- emitting electromagnetic radiation onto an object plane,
- modulating said electromagnetic radiation at said object plane in accordance to an input pattern description,
- relaying said electromagnetic radiation toward said workpiece,
- supplying an immersion medium to contact at least a portion of an objective lens of said lithographic system and at least a portion of said workpiece,

~~The method according to claim 23, further comprising the action of:~~

- ~~restricting a later extension of said contact by capillary forces.~~

25. (Currently amended) A method for patterning a workpiece arranged at an image plane and covered at least partly with a layer sensitive to electromagnetic radiation, including the actions of:

- emitting electromagnetic radiation onto an object plane,
- modulating said electromagnetic radiation at said object plane in accordance to an input pattern description,
- relaying said electromagnetic radiation toward said workpiece,
- contacting at least a portion of an objective lens of said lithographic system and at least a portion of said workpiece via ~~[[a]]~~ an immersion medium, wherein said contacting is restricted in a lateral direction of said workpiece by capillary forces.

26. (Previously presented) The method according to claim 25, further including the action of:

- supplying said immersion medium via an immersion medium reservoir.

27. (Original) The method according to claim 26, wherein said immersion medium is supplied through a porous or fibrous material.

28. (Currently amended) A method for patterning a workpiece arranged at an image

plane and covered at least partly with a layer sensitive to electromagnetic radiation, including the actions of:

- emitting electromagnetic radiation onto an object plane,
- modulating said electromagnetic radiation at said object plane in accordance to an input pattern description,
- relaying said electromagnetic radiation toward said workpiece,
- forming an immersion medium film to contact at least a portion of an objective lens of said lithographic system and at least a portion of said workpiece,
- supplying immersion medium to said immersion medium film to maintain its lateral dimensions while moving said objective lens over said workpiece,
- supplying focus air through an inlet positioned between an outer edge of the medium film and an outer edge of the objective lens, whereby focus of the objective lens is controlled by the focus air.

29. (New) The immersion lithographic system of claim 1, further including a focus air supply inlet positioned between an outer edge of the medium film and an outer edge of the objective lens.

30. (New) The immersion lithographic system of claim 1, further including a drying air supply inlet and suction outlet positioned between an outer edge of the medium film and an outer edge of the objective lens assembly and a focus air supply inlet positioned between the drying air supply inlet and the outer edge of the objective lens assembly.

31. (New) The method of claim 23, further including supplying focus air through an inlet positioned between an outer edge of the medium film and an outer edge of the objective lens, whereby focus of the objective lens is controlled by the focus air.

32. (New) The method of claim 23, further including supplying drying air through an inlet and removed through adjacent suction outlet positioned between an outer edge of the medium film and an outer edge of the objective lens assembly and supplying focus air through an inlet positioned between the drying air inlet and the outer edge of the objective lens assembly.

33. (New) The method of claim 28, further including drying air supplied through an inlet and removed through adjacent suction outlet positioned between an outer edge of the medium film and the focus air inlet.